

Notice of References Cited

Application/Control No.

09/836,711

Applicant(s)/Patent Under
Reexamination
WATANABE ET AL.

Examiner

Brian P. Egan

Art Unit

1772

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-2002/0129875	09-2002	Ikeda et al.	--
	B	US-2001/0026016	10-2001	Yoshida et al.	--
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N	WO 00/19792	04-2000	PCT	Nakahoshi et al.	English Translation
	O	EP 0877394	11-1998	EP	Kamei et al.	--
	P					
	Q					
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NON-PATENT DOCUMENTS

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	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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